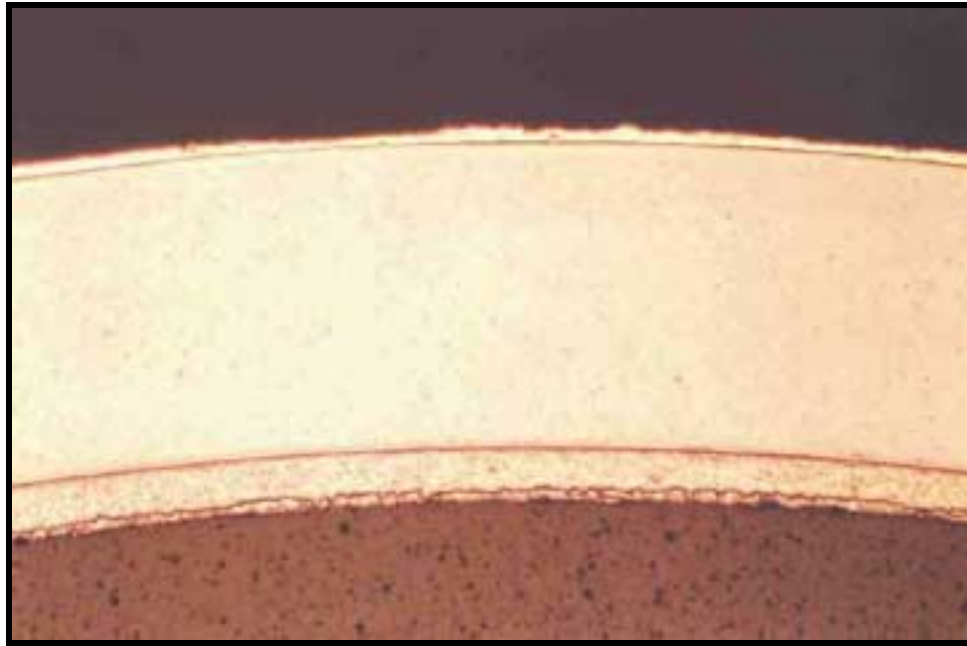


# MetPrep Preparation Procedure – No 200



## Electronic Component Ceramic Filter

Primary Grinding Stage	Surface	Abrasive	Pressure		Speed – Dir	Time
	Fixed Diamond	20 µm MB	Psi	N		
			5	25		
					500 – Comp	Until Planar

Additional Grinding Stages	Surface	Abrasive	Pressure		Speed – Dir	Time
	Planocloth H	9 µm (WB) PCD Diamond	Psi	N		
			5	25		
	Planocloth	1 µm (WB) PCD Diamond	5	25	250 – Comp	5 mins
	Planocloth	0.06 µm Silco	3	15	100 – Comp	10 mins

Polishing Stage	Surface	Abrasive	Pressure		Speed – Dir	Time
	Multicloth	0.06 µm Silco	Psi	N		
			3	15	100 – Comp	2 mins